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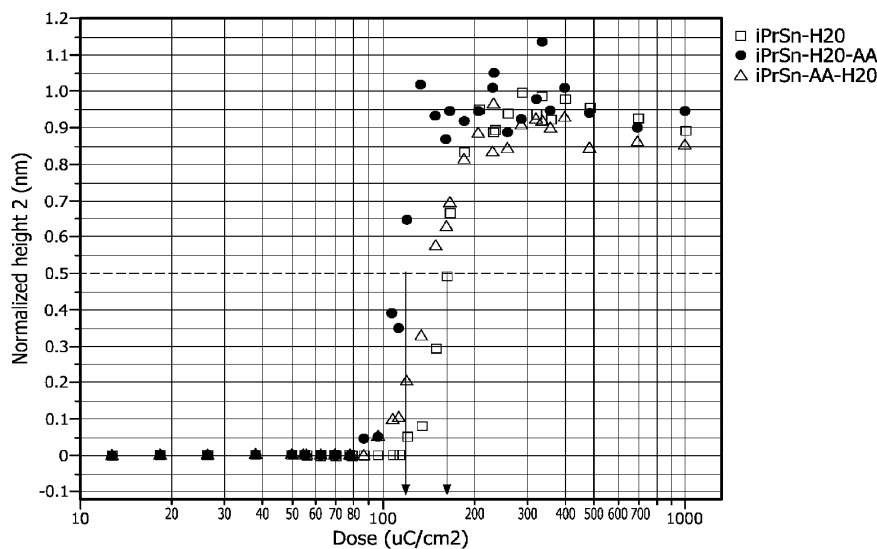


FIG. 1

(57) Abstract: The disclosed and claimed subject matter relates to a method for depositing tin-containing films. The method includes (i) contacting a substrate with organotin precursor vapor in a deposition reactor, (ii) purging the reactor vessel with inert gas, (iii) contacting the substrate with a water-containing vapor to form an organotin oxo network layer, (iv) purging the reactor vessel with inert gas, (v) contacting the substrate with a carboxylic acid-containing vapor and (vi) purging the reactor vessel with inert gas.

[Continued on next page]

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